

ABSTRACT OF THE DISCLOSURE

In a transparent laminate,  $n$  thin-film units ( $n=3$  or 4) are laminated unit by unit successively on a surface of a substrate, and a high-refractive-index transparent thin film is deposited on a surface of the laminate of the  $n$  thin-film units, each of the  $n$  thin-film units consisting of a high-refractive-index thin film and a silver transparent conductive thin film. When the silver transparent conductive thin films are deposited by a vacuum dry process, the temperature  $T$  (K) of the transparent substrate at the time of film deposition is set to be in a range  $340 \leq T \leq 410$ , whereby the transparent laminate having a standard deviation of visible light transmittance which is not larger than 5 % in a wave range of from 450 to 650 nm can be produced.